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ABSTRACT OF THE DISCLOSURE

A projection apparatus includes a charged particle beam source, a reduction lens, a charged particle shaping aperture having an arcuate opening, a collimator lens, and
5 first and second projection lenses. A charged particle beam emerging from the charged particle beam source irradiates a mask placed on a mask stage to transfer a pattern on the mask onto a sample on a sample stage. The first and second
10 projection lenses can move their first and second principal plane positions with an excitation strength ratio control circuit. An image distortion amount is thus corrected.